

Delete page 15, lines 14-18, and add, as follows:

B6
As for Examples 7-10, the under layer was formed to have a thickness of 20 nm by the sputtering method using an oxide target and in RF mode. As for Example 11, the under layer was formed to have a thickness of 20 nm by the CVD method just like Comparative Example 4.

IN THE CLAIMS

Please amend claims 1, 4-6 and 8, as follows:

B7
1.(amended) A glass article comprising an alkali-containing glass substrate, and a barrier film mainly formed of at least one of indium oxide and tin oxide, said barrier film being formed on a substantially entire outer surface of said alkali-containing glass substrate without operating as an electrode so that in case metal is deposited on the barrier film, diffusion of metal ions of the metal into the glass substrate is substantially prevented.

B8
4.(amended) A glass article as claimed in claim 3, wherein a surface electrical resistance of said insulating film is in a range from $1.0 \times 10^6 \Omega/\square$ to $1.0 \times 10^{16} \Omega/\square$.

5.(twice amended) A glass article as claimed in claim 3, wherein a surface electrical resistance of said insulating film is kept in the range from $1.0 \times 10^6 \Omega/\square$ to $1.0 \times 10^{16} \Omega/\square$ even after heating process at 550 °C for 1 hour.

6.(twice amended) A glass article as claimed in claim 3, further comprising an electrode film formed on said insulating film for forming a display panel.

Sub C
8.(amended) A glass substrate for a display comprising:

an alkali-containing glass substrate;
an under layer for preventing diffusion of alkali ions formed on a surface of said alkali-containing glass substrate;
a barrier film mainly formed of at least one of indium oxide and tin oxide, and deposited on a substantially entire outer surface of the under layer;